L Number	Hits	Search Text	DB	Time stamp
1	67	pad with (holes reliefs) with (radial radius)	USPAT	2002/05/10 12:40
2	7	pad with function near2 radius	USPAT	2002/05/10 12:27
3	2608	polishing adj pad	USPAT	2002/05/10 12:30
4	1913	(polishing adj pad) and (CMP (chemical adj mechanical adj polishing))	USPAT	2002/05/10 12:31
5	571	pad adj wear	USPAT	2002/05/10 12:31
6	2588	(relief hole) with determining	USPAT	2002/05/10 12:33
7	450	determining near2 wear	USPAT	2002/05/10 12:33
8	2608	polishing adj pad	USPAT	2002/05/10 12:34
9	150	451/56.ccor.	USPAT	2002/05/10 12:38
10	397	451/56.ccls.	USPAT	2002/05/10 12:38
11	16	(pad adj wear) WITH (monitoring measuring)	USPAT	2002/05/10 12:39
12	68	((polishing adj pad) and (CMP (chemical adj mechanical adj polishing))) and (pad adj wear)	USPAT	2002/05/10 12:39
13	1	((monitoring measuring determining) near2 wear) and ((polishing adj pad) with (relief hole grid))	USPAT	2002/05/10 12:39
14	63	pad with pattern with (radial radius)	USPAT	2002/05/10 12:40